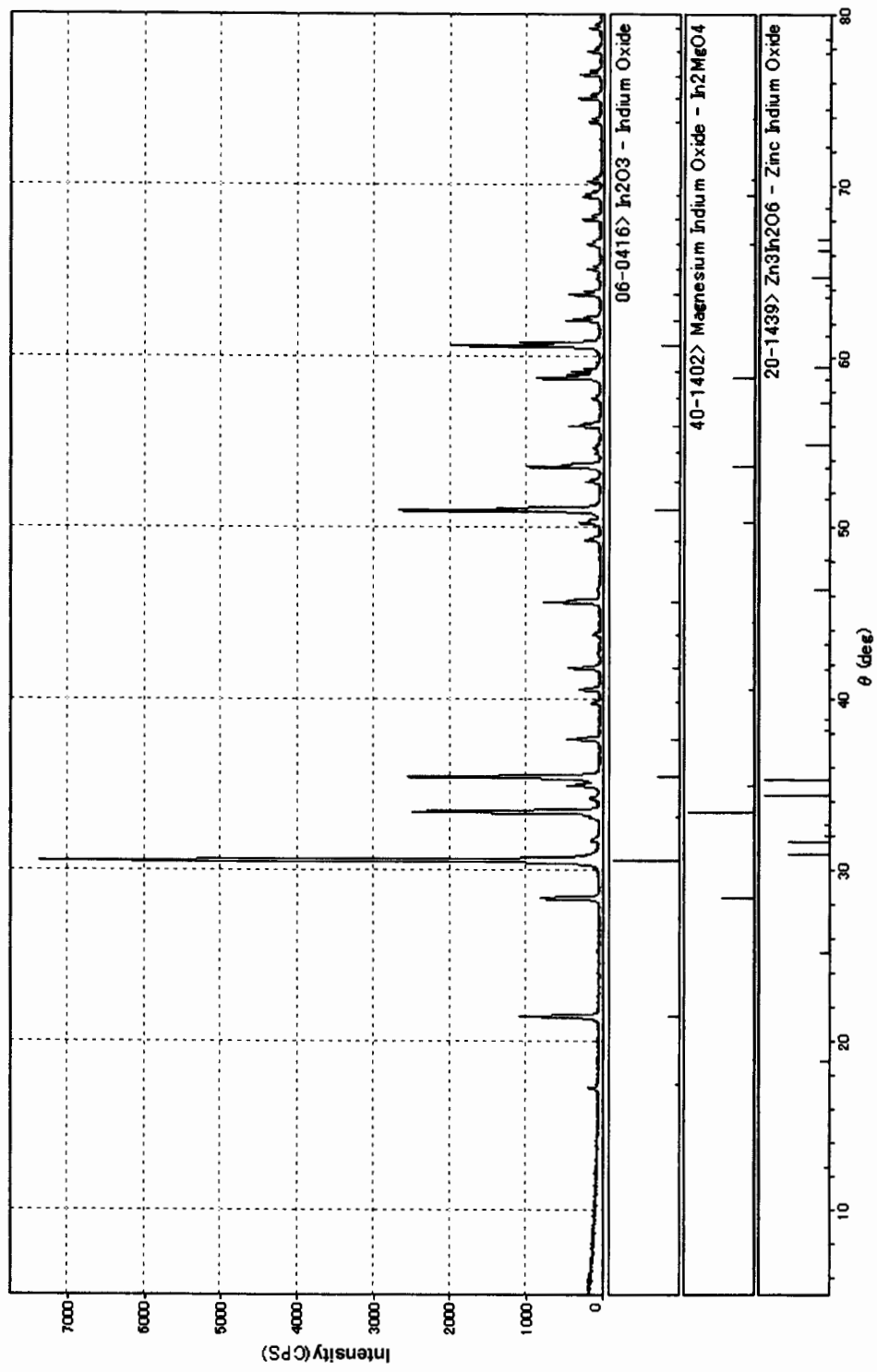


Fig.1

	[In] ([In] + [Zn] + [Mg])	[Zn] ([In] + [Zn] + [Mg])	[Mg] ([In] + [Zn] + [Mg])	[M] ([In] + [Zn] + [Mg] + [M])	[X] ([In] + [Zn] + [Mg] + X)	Relative density %	Bulk resistance mΩ cm	Generation nodules	Specific resistance of transparent electrode μΩ cm	Light transmittance		Etching residue
										400nm	450nm	
Example 1	0.92	0.06	0.02	—	—	97	8.6	Not generated	346	76	86	Not generated
Example 2	0.90	0.08	0.02	—	—	96	8.4	Not generated	368	77	86	Not generated
Example 3	0.90	0.06	0.04	—	—	97	8.5	Not generated	345	78	89	Not generated
Example 4	0.83	0.16	0.02	—	—	95	8.8	Not generated	325	75	86	Not generated
Example 5	0.92	0.06	0.02	Sn 0.0007 (700ppm)	—	95	3.1	Not generated	328	76	88	Not generated
Example 6	0.83	0.15	0.02	Sn 0.005 (5000ppm)	—	95	1.5	Not generated	316	77	87	Not generated
Example 7	0.875	0.08	0.02	Sn 0.025	—	97	0.53	Not generated	275	78	88	Not generated
Example 8	0.83	0.15	0.02	Zn 0.005 (5000ppm)	—	96	0.86	Not generated	286	77	87	Not generated
Example 9	0.83	0.15	0.02	Ge 0.005 (5000ppm)	—	96	0.92	Not generated	291	78	87	Not generated
Comparative Example 1	0.90	—	—	—	Sn 0.10	99	0.24	Generated	185	77	87	Generated
Comparative Example 2	0.84	—	—	—	Zn 0.16	96	4.8	Generated	295	70	83	Not generated

Fig.2



X-ray chart of target 1